



Atty. Dkt. No. AMAT/3415.Y1/CMP/QMP/RKK

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Re Application of:  
Thomas H. Osterheld  
  
Serial No.: 09/826,419  
  
Confirmation No.: 5039  
  
Filed: April 5, 2001  
  
For: Grid Relief In CMP  
Polishing Pad To  
Accurately Measure Pad  
Wear, Pad Profile and Pad  
Wear Profile

Group Art Unit: 3723

Examiner: David B. Thomas

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DEC 19 2002

TECHNOLOGY CENTER R3700

Commissioner for Patents  
Washington, D.C. 20231

Dear Sir:

## **RESPONSE TO OFFICE ACTION DATED OCTOBER 25, 2002**

In response to the Office Action dated October 25, 2002, having a shortened statutory period for response set to expire on January 25, 2003, please enter this response and reconsider the claims pending in the application for reasons discussed below. Although Applicant believes that no fee is due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/3415.Y1/CMP/CMP/RKK, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

## **IN THE CLAIMS:**

Please amend the claims as follows:

5. (Amended) A method for measuring wear of the thickness of a chemical mechanical polishing pad, the method comprising: